

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L3	81810	(cmp (chemical adj mechanical adj polish\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/03/15 16:17
L4	2237	slurry same (surfactant\$1 with (anionic cationic))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/03/15 16:17
L5	122	(polish\$3 etch\$3) with (prevent\$4 stop\$4 inhibit\$4) with (anionic cationic)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/03/15 16:18
L6	17	3 and 4 and 5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/03/15 15:48